ClassOne SRD Cleaning Procedure

1. Do a PRE particle check on a wafer.
2. Run a wafer through the SRD.
3. Run a POST particle check on that wafer.
   1. This will be our PRE- cleaning particle count.
4. Now perform a hydrogen peroxide 30% wash.
   1. Spray down the inside and outside. Especially near the vents that water is dispersed through.
5. Do the Hydrogen Peroxide wash 4X.
6. Now run a wafer through. Do a PRE and POST particle check.
   1. A good particle limit would be 50. (Clean Room)
7. If the wafer is in spec run TXRF on a couple wafers.